

酸化チタンを正孔コンタクトとして用いた 新型結晶シリコン太陽電池の開発

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Motivation

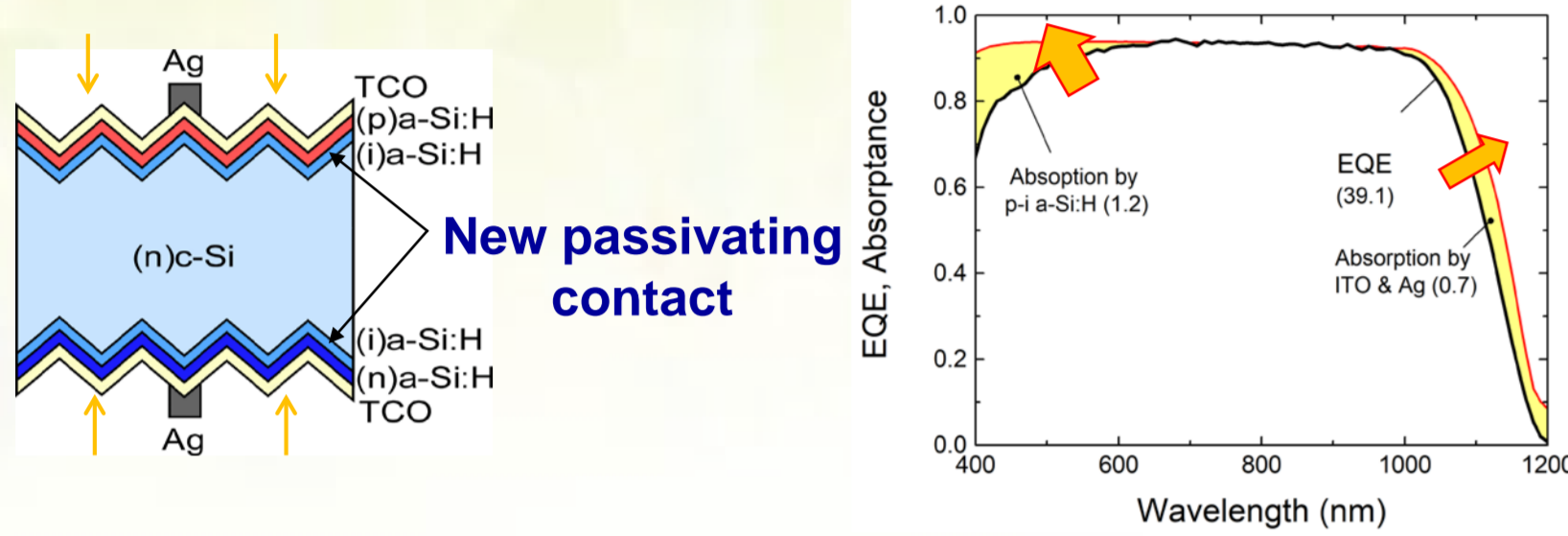
Novel passivating contacts

Bifacial SHJ

⊕ Excellent performance, bifaicality, outdoor performance

⊗ Parasitic absorption by a-Si:H

⊗ CAPEX (PECVD tool)



Low cost and transparent passivating contact that can replace a-Si:H

➢ Metal-oxide semiconductors

Non-Si passivating contacts

Metal oxides, nitrides, fluorides

Work function	low	low	?	high
Material	LiF _x	Ta ₂ N _x	TiO _x	MoO _x
Carrier selectivity	e ⁻	e ⁻	e ⁻	h ⁺
Buffer layers	a-Si:H	w/o	w/o	w/o
efficiency	~20%	20.1%	22.1%	21.1%
Structure				
Ref.	Bullock et al. Nat. Energy (2016) [1]	Yang et al. Adv. Energy Mater. (2018) [2]	Yang et al. Prog. Photovolt. (2017) [3]	This work [4]

- various electron/hole selective materials
- preferably buffer free
- preferably transparent if applied as window

TiO_x

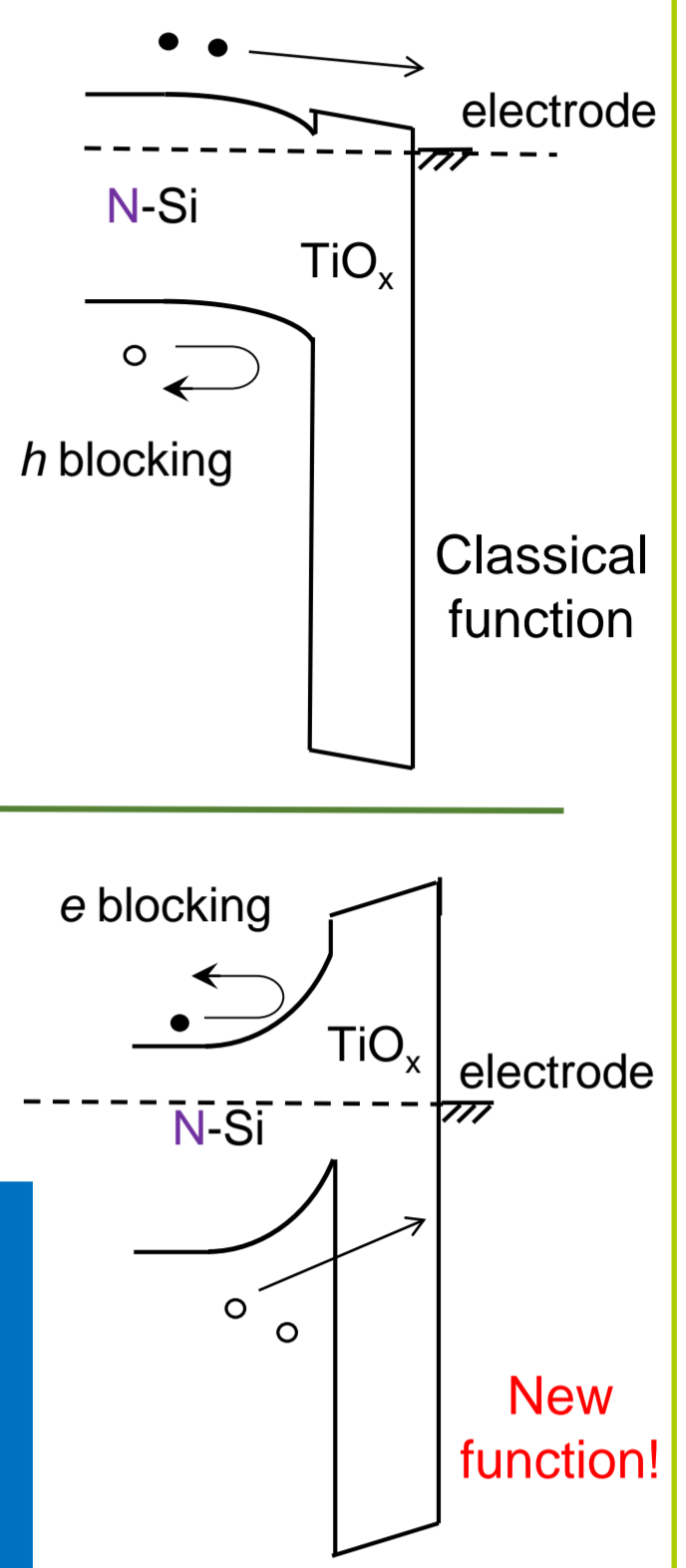
■ TiO_x (TiO₂) electron contact by thermal-ALD provides η=22.1% [3]

■ TiO_x used as electron contacts in non-Si PV [6]

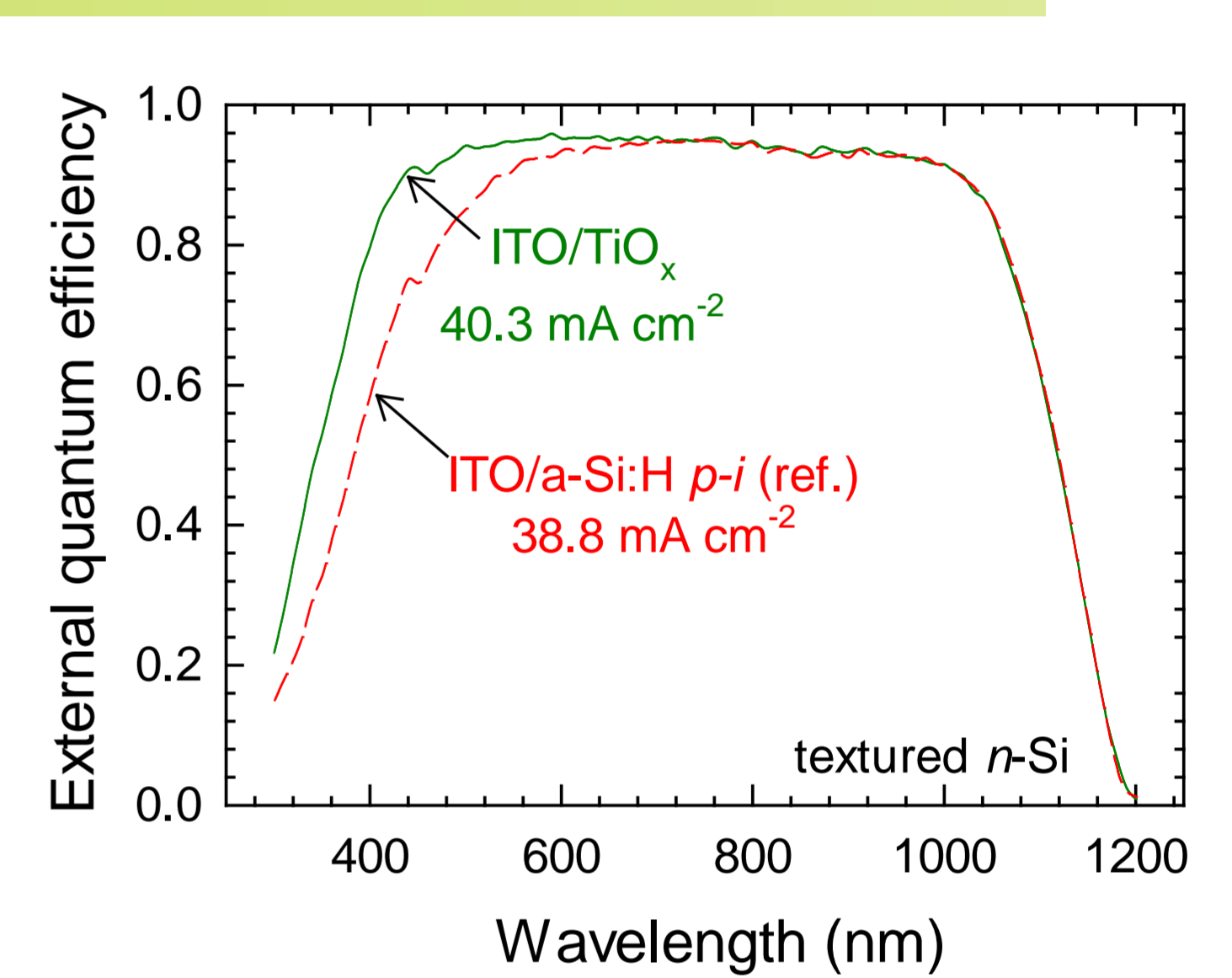
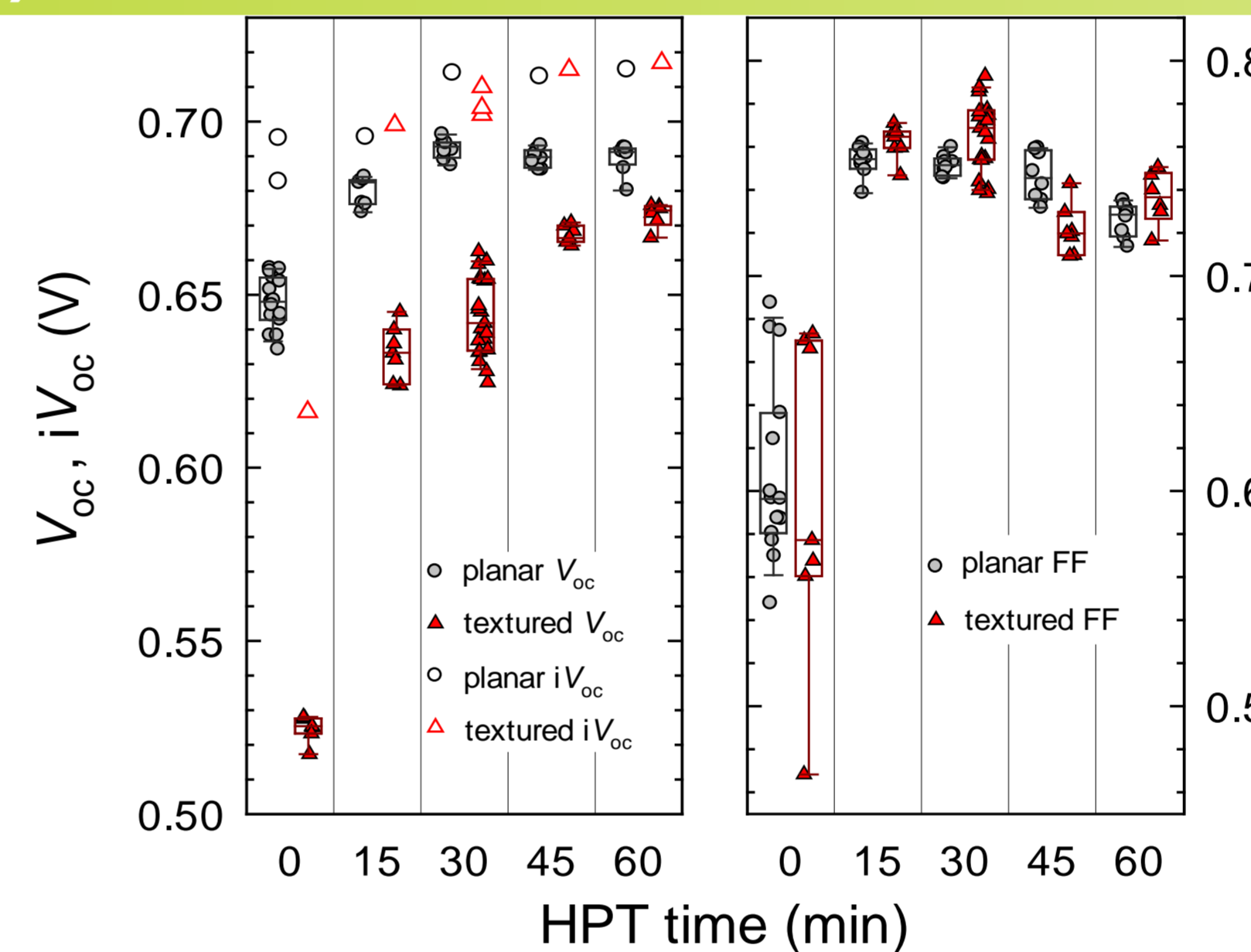
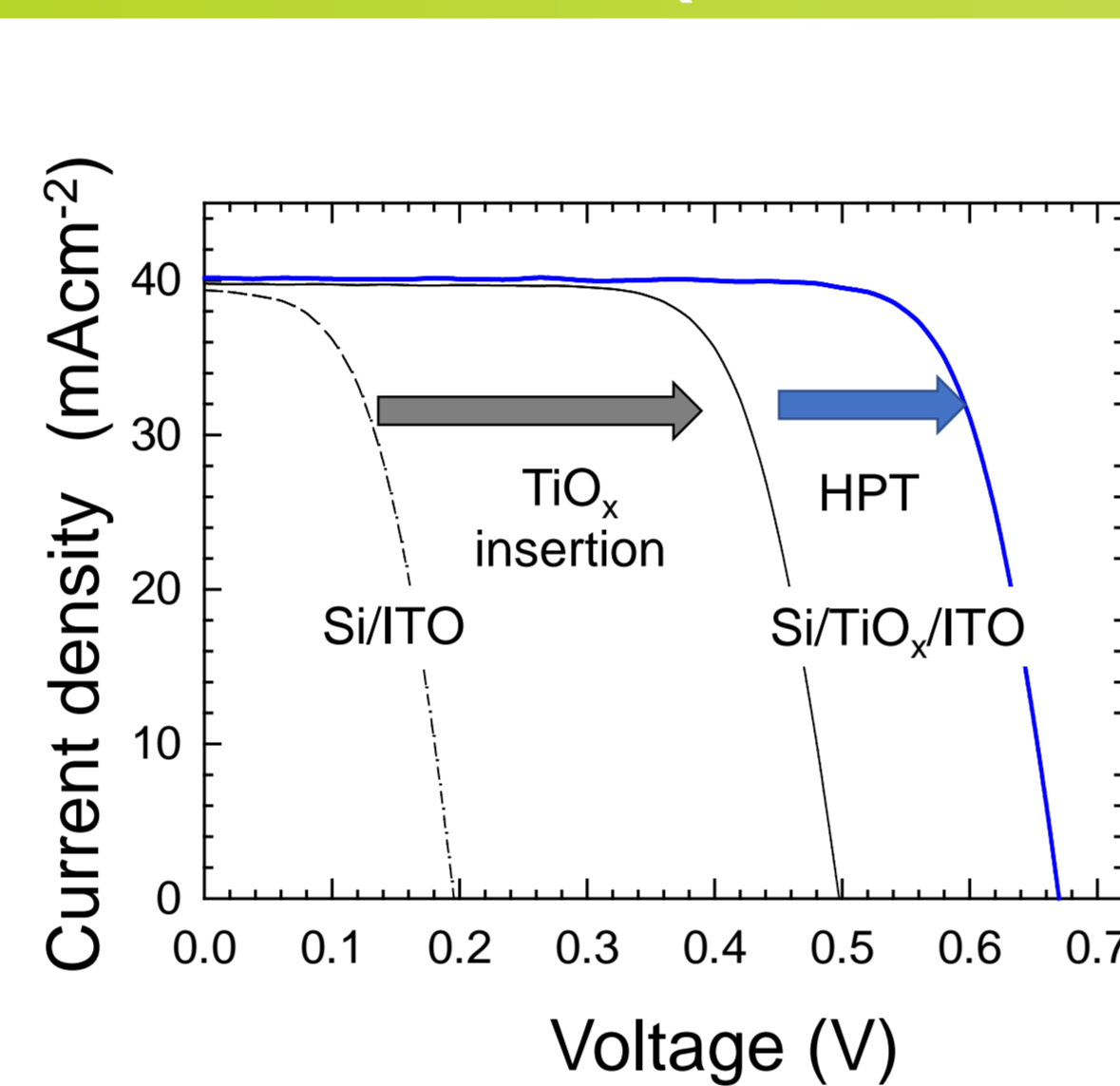
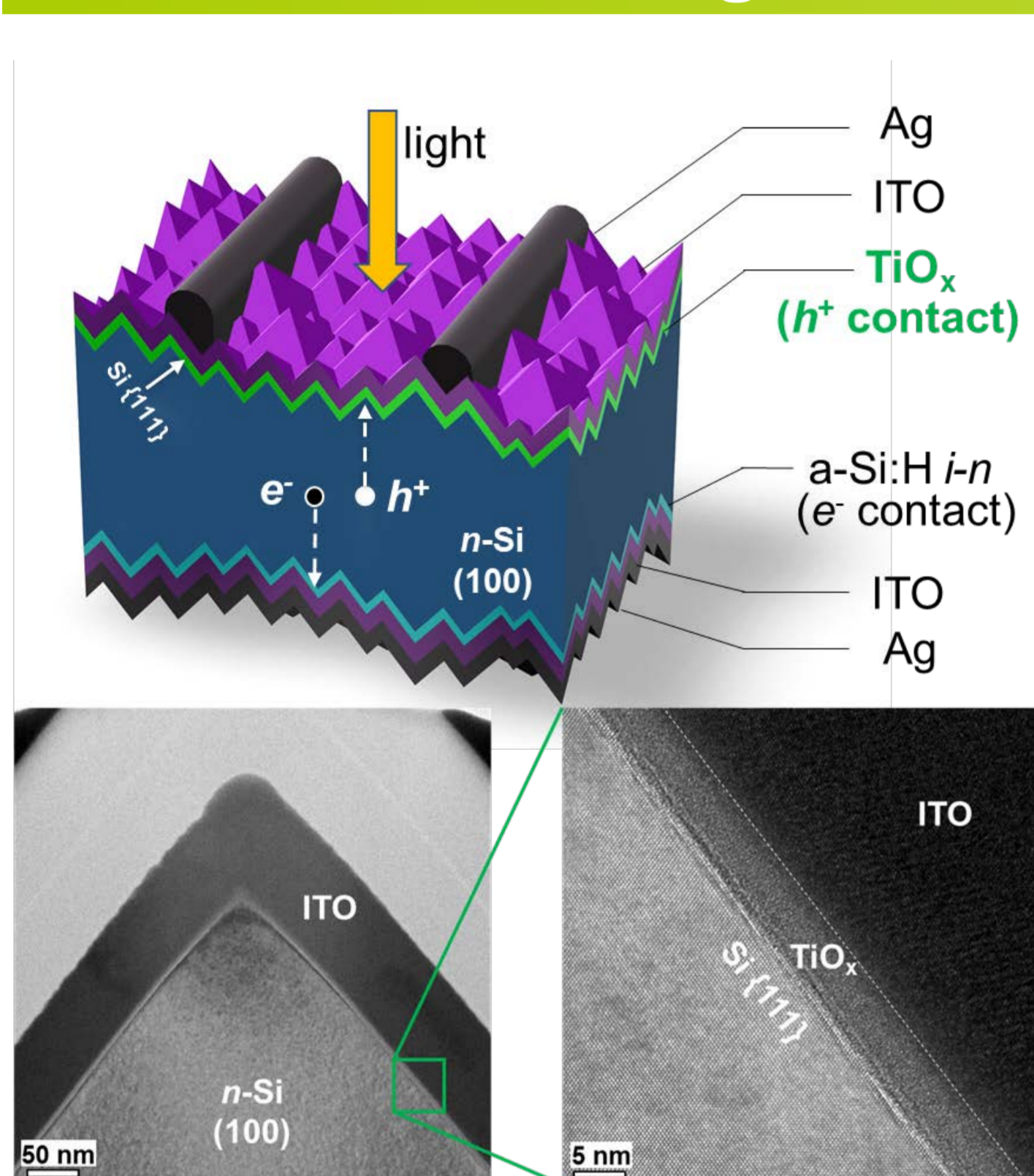
■ Electron selectively ascribed to the asymmetric band offset [7]

■ Recently, we find that TiO_x can be tuned to work as hole selective contact [8,9]

- Contradiction to the previous understanding...
- Can TiO_x actually work as hole transport layer in solar cells?



Solar cells featuring ALD-TiO_x hole contacts (textured Si)

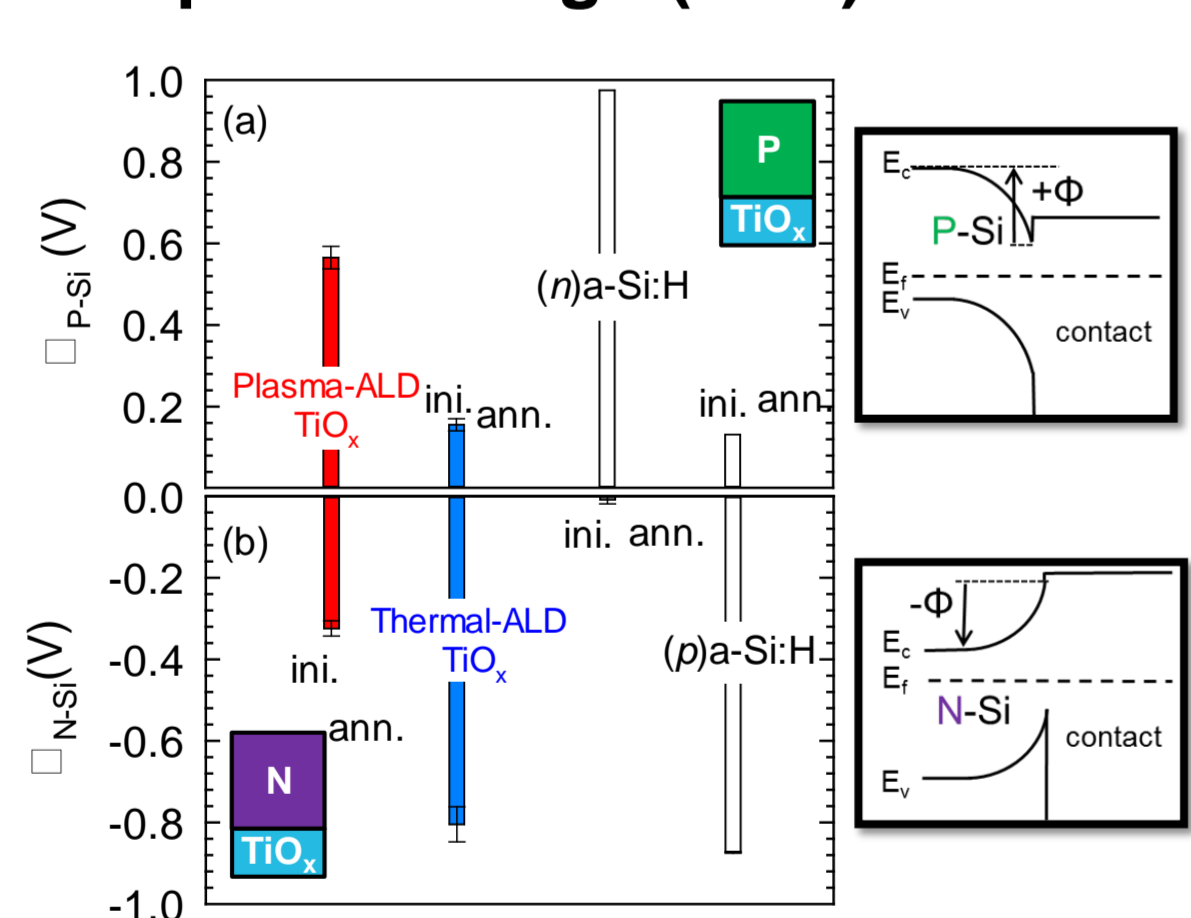


- Conformal deposition of TiO_x layer (5 nm) by thermal-ALD on Si pyramids
- TiO_x layer works as hole contact (emitter)
- Hydrogen plasma treatment (HPT) improves V_{oc} and FF significantly
- A 21.1% independently-confirmed efficiency is demonstrated

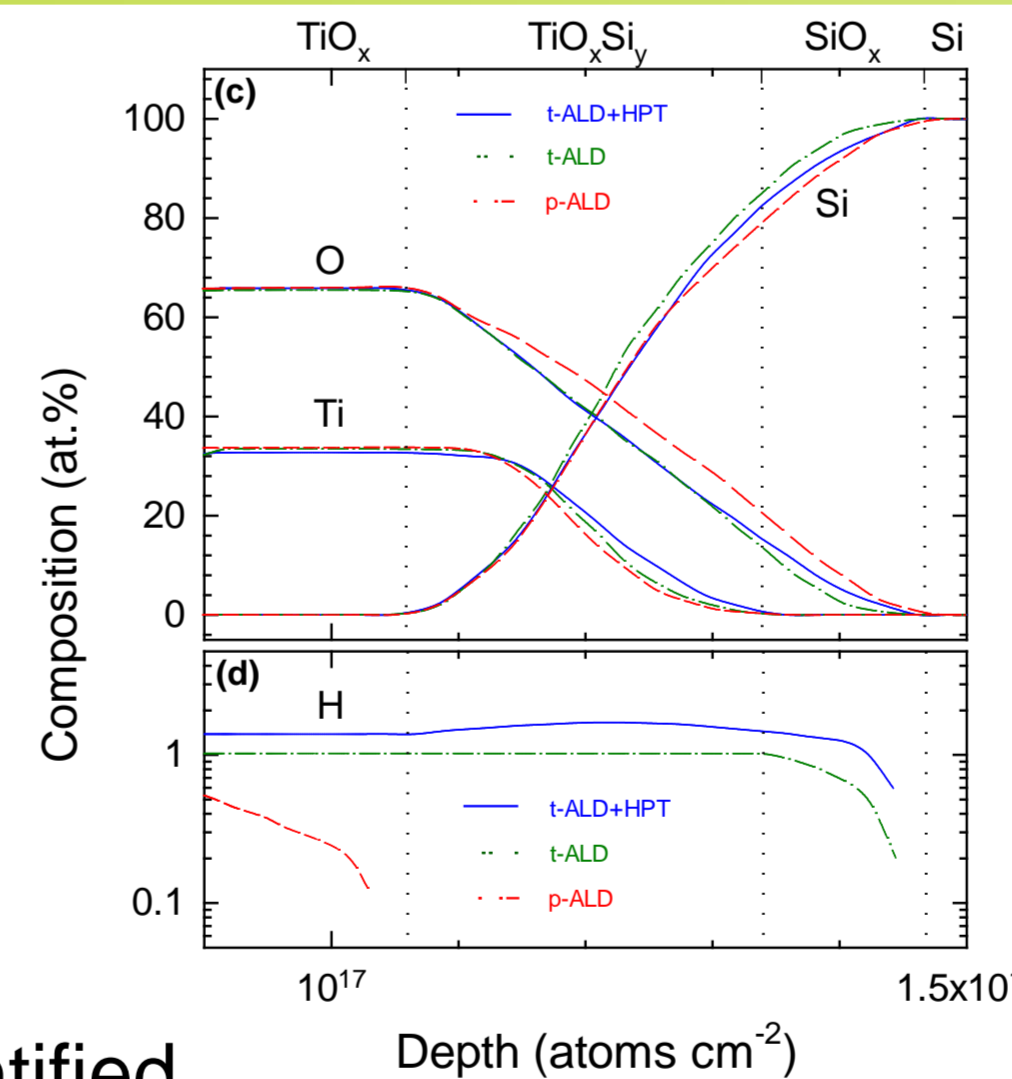
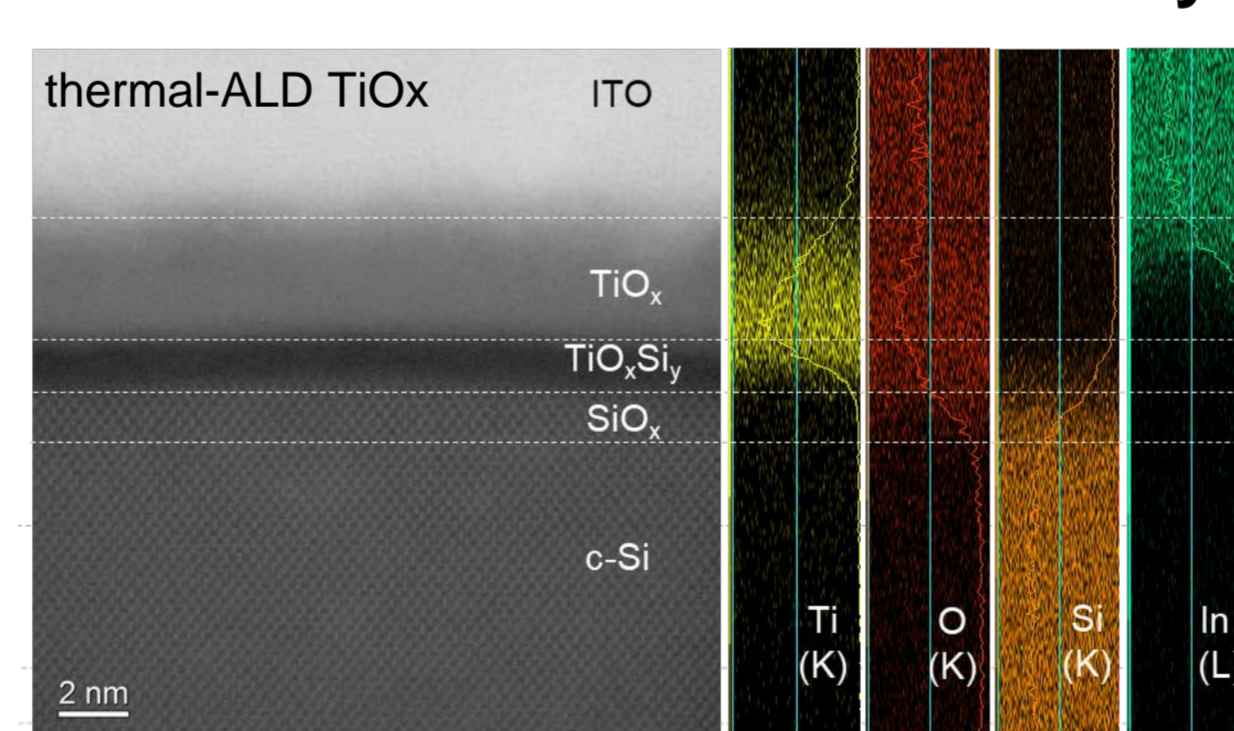
- Marked gain in blue response (ΔJ_{sc}~1.5 mAcm⁻²)
- UV induced degradation is an emerging issue

Origin of the hole selectivity and hole collection mechanism

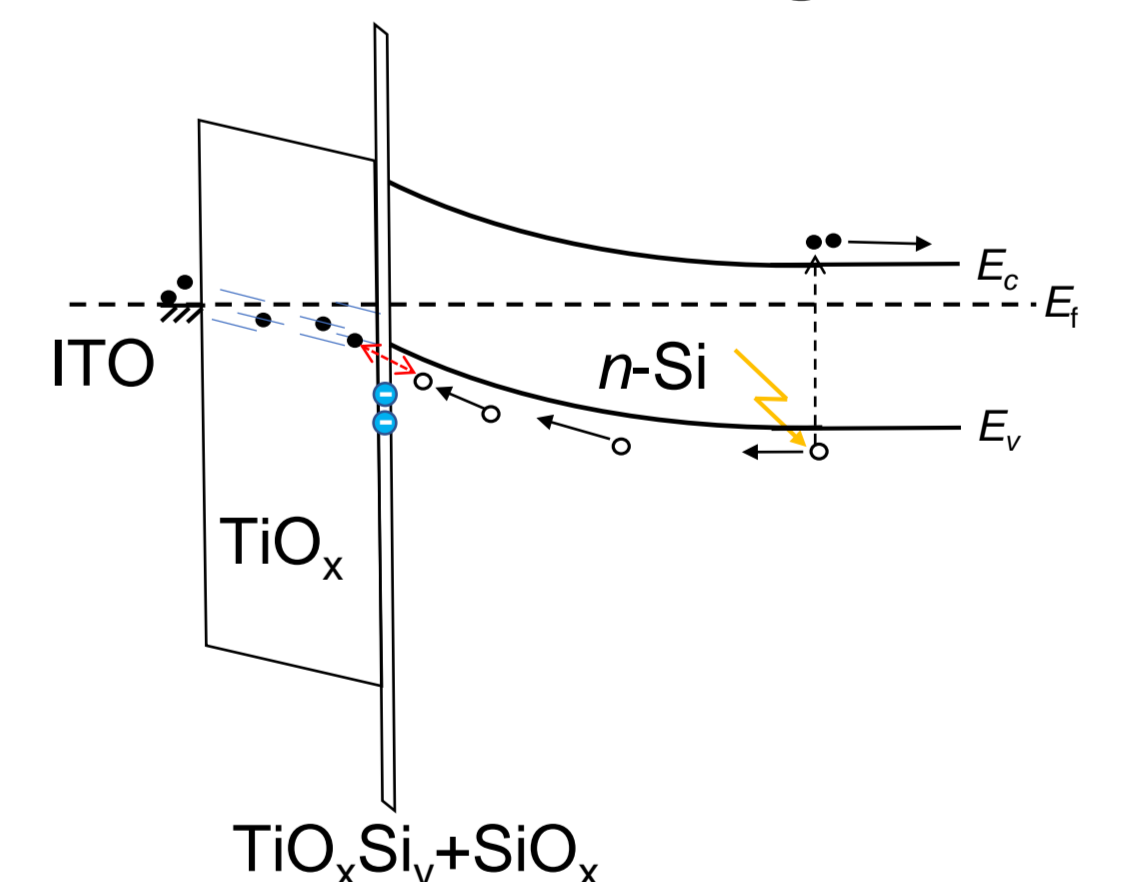
Surface photovoltage (SPV) measurement



TEM and RBS-ERDA analysis



Possible band diagram



- Opposite polarity of induced band bending (Φ) by two ALD processes
- C-V indicates negative fixed charge in thermal-ALD TiO_x [9]

- Intermixing (TiO_xSi_y) layer (~2 nm) identified
- Difference found in atomic profiles in the TiO_xSi_y layer → possible origin of the negative charge generation
- thermal-ALD TiO_x contains 1 at.% hydrogen → passivation mechanism
- HPT slightly modifies interface composition and increase H content >1 at.%

- Negative fixed charge and (high WF) ITO create induced-junction in n-Si
- Hole (electron) transport via the localized states in TiO_x

Conclusions

- TiO_x acting as an efficient hole selective passivating contact is demonstrated for textured Si.
- HPT drastically improves both passivation and hole selectivity.
- Parasitic absorption loss due to a-Si:H is almost completely removed thanks to the high transparency of TiO_x.
- A 21.1% confirmed efficiency is demonstrated.

Outlook

- Improving initial performance and UV tolerance.
- TiO_x/Si/TiO_x cell development and application for tandem devices.

References

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Acknowledgements

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